| | Application No. | Applicant(s) | |
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| Notice of Allowability | 10/816,560 Examiner | WANG ET AL. Art Unit | |
| | Cxammer | Artonit | |
| | Rodney G. McDonald | 1753 | |
| The MAILING DATE of this communication ap All claims being allowable, PROSECUTION ON THE MERITS herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3 | IS (OR REMAINS) CLOSED in this ap 35) or other appropriate communication RIGHTS. This application is subject | oplication. If not included n will be mailed in due course. THIS | |
| 1. This communication is responsive to <u>Amendment filed 9</u> | <u>9-5-07</u> . | | |
| 2. The allowed claim(s) is/are <u>1-17</u> . | | | |
| 3. Acknowledgment is made of a claim for foreign priority a) All b) Some* c) None of the: 1. Certified copies of the priority documents had 2. Certified copies of the priority documents had | ave been received. | | |
| Copies of the certified copies of the priority international Bureau (PCT Rule 17.2(a)). Certified copies not received: | documents have been received in this | national stage application from the | |
| Applicant has THREE MONTHS FROM THE "MAILING DATI noted below. Failure to timely comply will result in ABANDOI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. | E" of this communication to file a reply NMENT of this application. | complying with the requirements | |
| 4. A SUBSTITUTE OATH OR DECLARATION must be sub INFORMAL PATENT APPLICATION (PTO-152) which g | | | |
| 5. CORRECTED DRAWINGS (as "replacement sheets") m (a) including changes required by the Notice of Draftsport 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examine | erson's Patent Drawing Review(PTO —· | | |
| Paper No./Mail Date Identifying indicia such as the application number (see 37 CFF each sheet. Replacement sheet(s) should be labeled as such i | | | |
| 6. DEPOSIT OF and/or INFORMATION about the department attached Examiner's comment regarding REQUIREMEN | posit of BIOLOGICAL MATERIAL | must be submitted. Note the | |
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| Attachment(s) | e Maka series se | Datant Amaliantia | |
| Notice of References Cited (PTO-892) Dotice of Draftperson's Patent Drawing Review (PTO-948) | 5. Notice of Informal F | | |
| 3. Information Disclosure Statements (PTO/SB/08), | Paper No./Mail Da | Interview Summary (PTO-413), Paper No./Mail Date □ Examiner's Amendment/Comment | |
| Paper No./Mail Date4. Examiner's Comment Regarding Requirement for Deposi | t 8. ⊠ Examiner's Statem | ent of Reasons for Allowance | |
| of Biological Material | 9. 🗌 Other | Histor & Brilled | |
| | | RODNEY G. MCDONALD PRIMARY EXAMINER | |

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REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance:

Claims 1-12 are indicated as being allowable over the prior art because the prior art of record does not teach ionizing a sputtered material; and applying a first and a second bias voltage to a first and a second region of a substrate of a micro-electromechanical system (MEMS) to form a first and a second layer of a first and a second film stack of a first and a second film bulk acoustic resonators filter of the MEMS for a first and a second frequency band respectively, the first and second layers having first and second desired thicknesses, and the first and second bias voltages being applied in accordance with at least the first and second desired thicknesses, respectively.

Claims 13-17 are indicated as being allowable over the prior art because the prior art of record does not teach forming a first and a second layer of a first and a second film stack of a first and a second film bulk acoustic resonators filter for a first and a second frequency band, respectively, at a first point in time, for a micro-electromechanical system (MEMS), the first and second layers having a first and a second thicknesses respectively; ionizing a sputtered material; and applying a first and a second bias voltage to a first and a second region of a substrate of the MEMS to form a third and a fourth layer of the first and second film stacks, on top of the first and second layers, respectively, at a second point in time, subsequent to said first point in time, the third and fourth layers having third and fourth desired thicknesses, and the first

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and second bias voltages being applied in accordance with at least the first and second desired thicknesses.

The closest prior art of record to Pryor (U.S. Pat. 5,091,208) while teaching applying two separate biases to two different regions of a substrate holder fails to teach ionizing a sputtered material; and applying a first and a second bias voltage to a first and a second region of a substrate of a micro-electromechanical system (MEMS) to form a first and a second layer of a first and a second film stack of a first and a second film bulk acoustic resonators filter of the MEMS for a first and a second frequency band respectively, the first and second layers having first and second desired thicknesses, and the first and second bias voltages being applied in accordance with at least the first and second desired thicknesses, respectively. Furthermore Pryor also fails to teach forming a first and a second layer of a first and a second film stack of a first and a second film bulk acoustic resonators filter for a first and a second frequency band, respectively, at a first point in time, for a micro-electromechanical system (MEMS), the first and second layers having a first and a second thicknesses respectively; ionizing a sputtered material; and applying a first and a second bias voltage to a first and a second region of a substrate of the MEMS to form a third and a fourth layer of the first and second film stacks, on top of the first and second layers, respectively, at a second point in time, subsequent to said first point in time, the third and fourth layers having third and fourth desired thicknesses, and the first and second bias voltages being applied in accordance with at least the first and second desired thicknesses.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rodney G. McDonald whose telephone number is 571-272-1340. The examiner can normally be reached on M-TH with every Friday off..

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam X. Nguyen can be reached on 571-272-1342. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Rodney G. McDonald Primary Examiner Art Unit 1753

RM

September 17, 2007